

Title (en)
ELECTRON BEAM PHYSICAL VAPOR DEPOSITION APPARATUS AND CONTROL PANEL THEREFOR

Title (de)
ELEKTRONENSTRAHL-PVD VORRICHTUNG UND SEINE STEUERTAFEL

Title (fr)
DISPOSITIF DE DEPOT EN PHASE GAZEUSE PAR PROCEDE PHYSIQUE A FAISCEAU ELECTRONIQUE ET PANNEAU DE COMMANDE ASSOCIE

Publication
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Application
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Priority

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Abstract (en)
[origin: WO0111103A2] An electron beam physical vapor deposition apparatus (10) for producing a coating on an article (20). The apparatus (10) generally includes a coating chamber (12) that is operable at elevated temperatures and subatmospheric pressures. An electron beam gun (30) projects an electron beam (28) into the coating chamber (12) and onto a coating material (26) within the chamber (12), causing the coating material (26) to melt and evaporate. The operation of the EBPVD apparatus (10) is enhanced by a control panel (118) with which components of the apparatus (10) can be monitored and controlled. The control panel (118) includes a schematic of the apparatus (10) and its components, with indicia (120) of the components, visual indicators associated with the indicia (120) for indicating the operating status of the components, and controls (124) associated with the indicia (120) and adjacent the visual indicators for changing the operation of the corresponding component of the EBPVD apparatus (10).

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